



DATA SHEET  
NexSil 20NH4

## NexSil 20NH4 Colloidal Silica

NexSil 20NH4 is an ammonia-stabilized alkaline dispersion of 20 nm colloidal silica at 40% SiO<sub>2</sub> concentration in water. The particles are negatively charged and have a high specific surface area.

NexSil 20NH4 can be used in a wide variety of applications such as precision investment casting, metal surface treatment, textile treatment, catalyst binder or other applications where a very small particle size colloidal silica is required.

### TYPICAL PROPERTIES

|                                  |                 |
|----------------------------------|-----------------|
| Appearance:                      | Translucent Sol |
| Specific Gravity:                | 1.295           |
| SiO <sub>2</sub> , %:            | 39 – 41         |
| NH <sub>3</sub> , %:             | 0.0 – 0.30      |
| pH:                              | 9.3             |
| Viscosity, cP:                   | 10 – 25         |
| Na, ppm:                         | <1000           |
| Surface Area, m <sup>2</sup> /g: | 135             |

### FOR ADDITIONAL INFORMATION OR TO ORDER MATERIAL

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